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(54) MASTER DISK EXPOSURE DEVICE AND METHOD THEREFOR

(57) Abstract:

PROBLEM TO BE SOLVED: To provide a master disk exposure device capable of exposing a minute pit and a narrow groove with high precision and provided with a developing function.

SOLUTION: In this master disk exposure device 100, a master disk 19 coated with a photoresist film 20 is irradiated convergently with laser beams to form a desired pattern. A nozzle 210 fills water between a condensing lens 17 and the master disk 19 during the exposure. The condensing lens 17 increases in NA and functions as an immersion objective. With the nozzle arranged in piping for a water tank and a developer tank, and

with a valve installed that changes a feeding liquid to water or developer, the master disk aligner can also be used as a developing device.

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